CLAIMS (26800)

What is claimed is:

- 1. A method of forming a polymer on a surface with gaps, comprising the steps of:
 - (a) activating precursors with a pulsed plasma; and
- (b) polymerizing said precursors on a surface with gaps to form a polymer layer; said gaps having an aspect ratio of at least about 1 to 1 and said polymer layer filling said gaps without voids.
- 2. A method of forming a polymer on a surface with gaps, comprising the steps of:
 - (a) activating precursors with a pulsed plasma; and
- (b) polymerizing said precursors on a surface with gaps to form a polymer layer, said gaps with aspect ratios of at least 1 to 1, and said polymer layer filling said gaps except with voids about the centers of said gaps.
- 3. A dielectric gap filling structure, comprising:
- (a) a layer of fluorocarbon polymer on a surface with gaps, said gaps with aspect ratios of at least 1 to 1 and of width at most 0.3 um, and said polymer filling said gaps.